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Invention **COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME**I hereby certify that this English Language abstract of JP 06-148896 - 2 Pages

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(21)Application number : 04-327610 (71)Applicant : TOKYO OHKA KOGYO CO LTD

(22)Date of filing : 13.11.1992 (72)Inventor : WAKIYA KAZUMASA

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(54) COATING LIQUID FOR RESIST AND RESIST MATERIAL USING THAT

(57)Abstract:

PURPOSE: To prevent the reduction of dimensional accuracy of pattern caused by interference between irradiating light and reflected light from the substrate in a photoresist film by incorporating a water-soluble film forming component and a fluorine-base surfactant.

CONSTITUTION: This resist coating liquid contains a water-soluble film forming component and a fluorine-base surfactant, and the resist material has a interference preventing film consisting of this coating liquid. In this case, the water-soluble film forming component is not limited as far as the component has solubility with water and has transmitting property for irradiating light. For example, this component has such properties that a uniform coating film can be formed by an usual coating means such as spin coating, no modified layer is formed between a film of this coating liquid and a photoresist film when the coating liquid is applied on the photoresist film, and further, a film having small absorption coefft. and high transmittance which sufficiently transmits active rays can be formed. The fluorine-base surfactant is not limited, and preferably an anion type nonmetal ion surfactant is used.

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